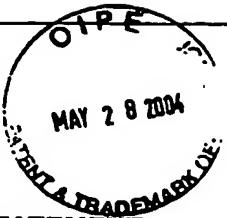


FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office



Atty. Dkt. No.	M#	Client Ref.
	306640	P-0390.010-US
Applicant: DIERICHS et al.		
Appln. No.: 10/719,009		
Filing Date: November 24, 2003		
Examiner: NOT ASSIGNED	Group Art Unit: 2874	

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: May 28, 2004

Page **1** of **1**

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
JM	AR 5,257,132	10/1993	Ceglio et al.			
BR						
CR						
DR						
ER						
FR						
GR						
HR						
IR						
JR						
KR						
LR						
MR						
NR						
OR						

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
PR								
QR								
RR								
SR								
TR								
UR								
VR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

WR				
XR				
YR				
ZR				
AAR				
BBR				
CCR				

Examiner **/John McPherson/** Date Considered: **06/21/2006**

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Applicant: DIERICHS et al.

Appn. No.: TO BE ASSIGNED

Filing Date: November 24, 2003

Date: November 24, 2003

Page **1** of **1**

Examiner: Group Art Unit:

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OR							

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
JM	PR	2001-100018	04/2001	JAPAN	MAEHARA HIROSHI	X			
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JM	WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," <i>J. Vac. Sci. Technol. B</i> 12(6):3833-3840, XP-002096163 (1994)					
	XR						
	YR						
	ZR						
	AAR						
	BBR						
	CCR						

Examiner **/John McPherson/** Date Considered: **06/21/2006**

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